Docket No.

240416US0DIV

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Masakazu KANECHIKA, et al.

SERIAL NO: 10/618,085

GAU: 28

2813

FILED:

July 14, 2003

**EXAMINER: NGUYEN** 

FOR:

METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE AND SEMICONDUCTOR DEVICE

## **INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97**

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

#### REFERENCES

The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.

☐ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

#### **RELATED CASES**

Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present
application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s)
is attached along with PTO 1449.

☐ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

#### **CERTIFICATION**

- Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

### DEPOSIT ACCOUNT

Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number <u>15-0030</u>. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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LIST OF REFERENCES CITED BY APPLICANT				Masakazu KANECHIKA, et al. FILING DATE July 14, 2003	GROUP 2813					
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	Hayakawa et al; "Mechanism of Residue Formation in Silicon Trench Etching Using a Bromine-Based Plasma," Jpn. J. Appl. AW Phys., Vol. 37 (1998) pp. 5-9.									
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